

ABSTRACT OF THE DISCLOSURE

In one embodiment, a solar cell is fabricated using an ink pattern as a mask for a processing step. The ink pattern may comprise an ink that is substantially devoid of particles that may scratch a surface on which the ink pattern is formed. The ink pattern
5 may be formed by screen printing. In one embodiment, the ink pattern is formed on an oxide layer and comprises an ink that is substantially free of silicon dioxide particles. The ink pattern may be employed as an etching or deposition mask, for example.